CWM PROGRESS REPORT

$\text{VO}_2$ THIN FILM OPTICAL STUDIES

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Vanadium dioxide is a paradigm of strongly correlated oxides and shows many intriguing properties that are still not understood and remain great intellectual challenges.

VO₂ has a metal–semiconductor transition at ~340 K, just above ambient temperature. The low-temperature semiconducting phase has a monoclinic crystal structure, while the metallic phase has a rutile structure above the transition temperature.

Across the metal-insulator transition (MIT), the resistivity changes by more than four orders of magnitude and the optical properties are completely modified over a very broad frequency range. The MIT in VO₂ combines the properties of a pure Mott Hubbard electronic transition with those of a Peierls structural transition.

The electronic character of the Mott transition is responsible for the extreme speed of the optical switching that has been observed.

Understanding this transition and how to control it is a current challenge for both theory and experimental condensed matter physics.
Experimental results

• We have investigated VO$_2$ films grown on sapphire.

• The optical measurements were carried out on 85 nm thick VO$_2$ films grown on c-plane sapphire. The films studied were strongly textured with (020) // (0001) sapphire.

• The measurements were performed using different laser wavelengths.
REFLECTIVITY AND TRANSMITTANCE MEASUREMENTS ON VO$_2$

Lasers used: IR laser: 1520 nm; Ti-Sapphire: 800 nm; Red laser: 632.7 nm; Green laser: 500 nm; Blue laser: 405 nm
Preliminary pump-probe experiments

We measured the amplitude of the VO2 transmittance modulation when pumping with green laser modulated at 44 Hz vs. temperature.
We note that the maximum signal is found when the slope of the transmittance is maximum:
IMPROVING THE ALIGNMENT AND OVERLAP OF BOTH LASERS IMPROVED DRASTICALLY THE SIGNAL
Ti-SAPPHIRE LASER WAS USED AS PUMP LASER

Again the signal follows the derivative of the transmittance curve.
VO₂ thin films thicknesses studies

49.5nm, 71.5nm and 101nm.

IR (λ=1520nm) transmission: it clearly shows an optical transmittance change up to 40% during the MIT for all the three VO₂ thin film samples.
Surface plasmon polaritons

• SPR Investigated in Kretschmann configuration while heating the sample above its MIT so that it is in its conducting phase.
Temperature-dependence of SPR in 49.5nm VO$_2$ thin film in the IR region

(a) Experimental

(b) Simulation
Experimental results (a) agree very well with the simulations (b). The SPR excitation strongly depends on film thickness. The thinner films (49.5 and 71.5 nm) show higher absorption due to stronger SPR excitation; for the thicker film (101 nm), SPR signal decreases since most of the light is absorbed by the film and cannot reach the VO$_2$/air interface.
Time resolved MIT studies

![Graph showing reflectivity over time for different power levels]

- Reflectivity (arbitrary units)
- t (ps)

Legend:
- 20mW
- 30mW
- 40mW
- 50mW
- 60mW
Average of four measurements at same power
THz vs IR studies of MIT

Equation: \[ y = A_2 + (A_1 - A_2)(1 + \exp((x-x_0)/dx)) \]

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<tr>
<th>Adj. R-Square</th>
<th>Value</th>
<th>Standard Error</th>
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<tr>
<td>Norm THz A1</td>
<td>0.90252</td>
<td>0.01423</td>
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<tr>
<td>Norm THz A2</td>
<td>9.92339E-11</td>
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<tr>
<td>Norm THz x0</td>
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<tr>
<td>Norm THz dx</td>
<td>0.22425</td>
<td>2.09148E6</td>
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Equation: \[ y = A_2 + (A_1 - A_2)(1 + \exp((x-x_0)/dx)) \]

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<tr>
<th>Adj. R-Square</th>
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<td>Norm IR A1</td>
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<td>Norm IR A2</td>
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<td>Norm IR x0</td>
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<td>Norm IR dx</td>
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